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CA INDEXING COPYRIGHT (C) 2003 AMERICAN CHEMICAL SOCIETY (ACS)

=> s Ong, Beng S./in

'IN' IS NOT A VALID FIELD CODE
L1 140 ONG, BENG S./IN

=> s 11 and polythiophene#

L2 0 L1 AND POLYTHIOPHENE#

=> s polythiophene#

L3 4806 POLYTHIOPHENE#

=> s 13 and tetrahydrofuran

L4 1218 L3 AND TETRAHYDROFURAN

=> s 14 and diphenyl phosphinoethane?

L5 0 L4 AND DIPHENYL PHOSPHINOETHANE?

=> s 14 and (dichloro-nickel or dichloronickel)

L6 3 L4 AND (DICHLORO-NICKEL OR DICHLORONICKEL)

=> d 16 1-3

L6 ANSWER 1 OF 3 PCTFULL COPYRIGHT 2003 Univentio

Full
Text

AN 2003001616 PCTFULL ED 20030115 EW 200301
TIEN LIGHT EMITTING MATERIAL AND ORGANIC LIGHT-EMITTING DEVICE
TIFR MATERIAU PHOTOEMETTEUR ET DISPOSITIF PHOTOEMETTEUR ORGANIQUE
IN TAKEUCHI, Masataka, Corporate R & D Center, Showa Denko K.K., 1-1,
Ohnodai 1-chome, Midori-ku, Chiba-shi, Chiba 267-0056, JP [JP, JP];
NAIJO, Shuichi, Corporate R & D Center, Showa Denko K.K., 1-1, Ohnodai
1-chome, Midori-ku, Chiba-shi, Chiba 267-0056, JP [JP, JP];
ITO, Naoko, Corporate R & D Center, Showa Denko K.K., 1-1, Ohnodai
1-chome, Midori-ku, Chiba-shi, Chiba 267-0056, JP [JP, JP];
SHIRANE, Koro, Corporate R & D Center, Showa Denko K.K., 1-1, Ohnodai
1-chome, Midori-ku, Chiba-shi, Chiba 267-0056, JP [JP, JP];
IGARASHI, Takeshi, Corporate R & D Center, Showa Denko K.K., 1-1,
Ohnodai 1-chome, Midori-ku, Chiba-shi, Chiba 267-0056, JP [JP, JP];

PA TAKAHASHI, Yoshiaki, Corporate R & D Center, Showa Denko K.K., 1-1, Ohnodai 1-chome, Midori-ku, Chiba-shi, Chiba 267-0056, JP [JP, JP]; KAMACHI, Motoaki, Corporate R & D Center, Showa Denko K.K., 1-1, Ohnodai 1-chome, Midori-ku, Chiba-shi, Chiba 267-0056, JP [JP, JP] SHOWA DENKO K.K., 13-9, Shiba Daimon 1-chome, Minato-ku, Tokyo 105-8518, JP [JP, JP], for all designates States except US; TAKEUCHI, Masataka, Corporate R & D Center, Showa Denko K.K., 1-1, Ohnodai 1-chome, Midori-ku, Chiba-shi, Chiba 267-0056, JP [JP, JP], for US only; NAIJO, Shuichi, Corporate R & D Center, Showa Denko K.K., 1-1, Ohnodai 1-chome, Midori-ku, Chiba-shi, Chiba 267-0056, JP [JP, JP], for US only; ITO, Naoko, Corporate R & D Center, Showa Denko K.K., 1-1, Ohnodai 1-chome, Midori-ku, Chiba-shi, Chiba 267-0056, JP [JP, JP], for US only; SHIRANE, Koro, Corporate R & D Center, Showa Denko K.K., 1-1, Ohnodai 1-chome, Midori-ku, Chiba-shi, Chiba 267-0056, JP [JP, JP], for US only; IGARASHI, Takeshi, Corporate R & D Center, Showa Denko K.K., 1-1, Ohnodai 1-chome, Midori-ku, Chiba-shi, Chiba 267-0056, JP [JP, JP], for US only; TAKAHASHI, Yoshiaki, Corporate R & D Center, Showa Denko K.K., 1-1, Ohnodai 1-chome, Midori-ku, Chiba-shi, Chiba 267-0056, JP [JP, JP], for US only; KAMACHI, Motoaki, Corporate R & D Center, Showa Denko K.K., 1-1, Ohnodai 1-chome, Midori-ku, Chiba-shi, Chiba 267-0056, JP [JP, JP], for US only AG OHIE, Kunihisa, Ohie Patent Office, Horiguchi No.2 Bldg. 7F, 2-6, Nihonbashi-Ningyocho 2-chome, Chuo-ku, Tokyo 103-0013, JP LAF English LA English DT Patent PI WO 2003001616 A2 20030103 DS W: AE AG AL AM AT AU AZ BA BB BG BR BY BZ CA CH CN CO CR CU CZ DE DK DM DZ EC EE ES FI GB GD GE GH GM HR HU ID IL IN IS KE KG KR KZ LC LK LR LS LT LU LV MA MD MG MK MN MW MX MZ NO NZ OM PH PL PT RO RU SD SE SG SI SK SL TJ TM TN TR TT TZ UA UG US UZ VN YU ZA ZM ZW RW (ARIPO): GH GM KE LS MW MZ SD SL SZ TZ UG ZM ZW RW (EAPO): AM AZ BY KG KZ MD RU TJ TM RW (EPO): AT BE CH CY DE DK ES FI FR GB GR IE IT LU MC NL PT SE TR RW (OAPI): BF BJ CF CG CI CM GA GN GQ GW ML MR NE SN TD TG AI WO 2002-JP6139 A 20020620 PRAI JP 2001-2001-186120 20010620 JP 2001-2001-188183 20010621 US 2001-60/301,844 20010702 US 2001-60/302,372 20010703 JP 2001-2001-241647 20010809 JP 2001-2001-263525 20010831 US 2001-60/317,115 20010906 JP 2001-2001-306282 20011002 US 2001-60/330,815 20011031 JP 2001-2001-345136 20011109 JP 2001-2001-350076 20011115 JP 2001-2001-369529 20011204 US 2001-60/337,157 20011210 US 2001-60/337,160 20011210 US 2001-60/337,161 20011210 JP 2002-2002-80456 20020322 JP 2002-2002-90590 20020328 ICM H01L051-30

L6 ANSWER 2 OF 3 USPATFULL

Full Citing
Text References

AN 2003:93810 USPATFULL
TI Luminescent element material, luminescent element, ethylene derivative having n-containing 7-membered ring, and benzoazepine derivative

IN Sato, Tadahisa, Kanagawa, JAPAN
 Okada, Hisashi, Kanagawa, JAPAN
 PA FUJI PHOTO FILM CO., LTD. (non-U.S. corporation)
 PI US 2003065171 A1 20030403
 AI US 2002-141001 A1 20020509 (10)
 RLI Division of Ser. No. US 1999-413848, filed on 7 Oct 1999, GRANTED, Pat.
 No. US 6413657
 PRAI JP 1998-285508 19981007
 JP 1999-86607 19990329
 DT Utility
 FS APPLICATION
 LN.CNT 1326
 INCL INCLM: 540/587.000
 INCLS: 428/690.000; 428/917.000; 313/504.000; 313/506.000; 252/301.350
 NCL NCLM: 540/587.000
 NCLS: 428/690.000; 428/917.000; 313/504.000; 313/506.000; 252/301.350
 IC [7]
 ICM: C07D223-18
 ICS: C09K011-06; H05B033-12
 CAS INDEXING IS AVAILABLE FOR THIS PATENT.

L6 ANSWER 3 OF 3 USPATFULL

Full Text	Citing References
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AN 2002:160473 USPATFULL
 TI Benzoazepine derivative polymers as luminescent element materials
 IN Sato, Tadahisa, Kanagawa, JAPAN
 Okada, Hisashi, Kanagawa, JAPAN
 PA Fuji Photo Film Co., Ltd., Kanagawa, JAPAN (non-U.S. corporation)
 PI US 6413657 B1 20020702
 AI US 1999-413848 19991007 (9)
 PRAI JP 1998-285508 19981007
 JP 1999-86607 19990329
 DT Utility
 FS GRANTED
 LN.CNT 1283
 INCL INCLM: 428/690.000
 INCLS: 428/500.000; 428/917.000; 526/259.000; 313/504.000; 313/506.000;
 257/040.000; 257/103.000; 252/301.350
 NCL NCLM: 428/690.000
 NCLS: 252/301.350; 257/040.000; 257/103.000; 313/504.000; 313/506.000;
 428/500.000; 428/917.000; 526/259.000
 IC [7]
 ICM: H05B033-12
 ICS: C09K011-06; C08F026-06
 EXF 428/690; 428/704; 428/917; 428/500; 428/523; 313/504; 313/506;
 252/301.35; 257/40; 257/103; 526/259; 540/576
 CAS INDEXING IS AVAILABLE FOR THIS PATENT.

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